

半金属 Fe_3O_4 薄膜的制备工艺探索

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摘要 半金属材料 Fe_3O_4 是一种新型的功能自旋电子材料, 由于其具有百分之百的自旋极化率而备受关注.

但由于铁元素存在多种价态的氧化物, 使得制备单一成分的 Fe_3O_4 非常困难,

因而本文着重对磁控反应溅射制备单一成分的 Fe_3O_4 薄膜进行了研究, 探索了晶化温度对薄膜结构的影响,

并通过引入缓冲层Ta对其性能进行改善, 得到了反应溅射制备半金属 Fe_3O_4 的最优条件. 另外,

通过对所制备的 Fe_3O_4 薄膜磁电阻效应的测试, 发现多晶 Fe_3O_4 具有同单晶 Fe_3O_4 薄膜类似的负磁电阻效应, 因此有望将其应用到自旋电子器件中.

关键词 [半金属材料](#) [自旋电子材料](#) [Fe3O4薄膜](#)

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Preparation of Half-metallic Fe_3O_4 Films

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Abstract Half-metallic magnetic material Fe_3O_4 is a new kind of spintronics material, which can provide 100% spin polarization. The Fe element has many electronic valences, so the pure Fe_3O_4 is difficult to prepare. Therefore, in this paper we mainly focused on finding the optimal way to fabricate pure Fe_3O_4 film. Half-metallic Fe_3O_4 films grown on Si (100) substrates were prepared by DC magnetron reactive sputtering. The annealing temperatures were investigated carefully, and the polycrystalline Fe_3O_4 films fabricated on Ta buffer layer shown better properties than the film directly sputtering on Si substrate. The optimum condition for the formation of polycrystalline Fe_3O_4 under DC magnetron reactive sputtering was found. The negative magnetoresistance of polycrystalline Fe_3O_4 was also tested, and showed a very weak saturation trend as the single-crystalline Fe_3O_4 films.

Key words [half-metallic material](#) [spintronic material](#) [Fe3O4 thin film](#)

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